

Customer No.: 31561
Docket No.: 10573-US-PA
Application No.: 10/604,793

AMENDMENTS

In The Claims:

1. (currently amended) A wafer surface ion sampling system, comprising:

a sampling chamber, comprised an upper part and a lower part, wherein the upper part accommodates a wafer, and the lower part has a funnel shape and comprises an extract solution collection opening;

a plurality of wafer carrier beams for holding the wafer, arranged around an upper part of a sidewall of the sampling chamber dispersedly, wherein each wafer carrier beam comprises a first wafer anchoring pin disposed on a peripheral surface of the wafer carrier beam, wherein the wafer anchoring pin extends in a first direction different from the direction which the wafer carrier beam extends, and each of the wafer carrier beams extends from the upper sidewall to the inside of the sampling chamber and passes the upper sidewall of the sampling chamber to the outside of the sampling chamber;

an extraction liquid spraying apparatus, disposed at a top part of the sampling chamber to spray an extraction liquid on a surface of the wafer; and

an extraction liquid supply apparatus, connected to the extraction liquid spraying apparatus to provide the extraction liquid to the extraction liquid spraying apparatus.

Claims 2-3. (canceled)

Customer No.: 31561
Docket No.: 10573-US-PA
Application No.: 10/604,793

4. (previously presented) The system of claim 3, wherein each of the wafer carrier beams further comprises a rotating handle disposed on the one end of the wafer carrier beam at the outside of the sampling chamber.

5. (previously presented) The system of claim 1, wherein the peripheral surface of the wafer carrier beam further comprises a second wafer anchoring pin that extends in a second direction, wherein the second direction is different from the first direction.

6. (previously presented) The system of claim 1, wherein there are at least three wafer carrier beams.

7. (currently amended) The system of claim 1, wherein at least a height of one of the wafer carrier beams is lower ~~that~~ than a height of the other wafer carrier beams.

8. (original) The system of claim 1, wherein the extraction liquid spraying apparatus comprises a plurality of spray nozzles or nebulizers, evenly disposed at the top part of the sampling chamber.

9. (original) The system of claim 1, wherein the extraction liquid supply apparatus further comprises a temperature adjustment device to control a temperature of the extraction liquid.

10. (original) The system of claim 1 further comprising a cleaning/drying apparatus, wherein the cleaning/drying apparatus comprises:

a cleaning/drying spray nozzle, disposed in the sampling chamber to spray a cleaning solution or a fluid into the sampling chamber;

Customer No.: 31561
Docket No.: 10573-US-PA
Application No.: 10/604,793

a cleaning solution supply apparatus, connected to the cleaning/spray nozzle to supply the cleaning solution to the cleaning/drying spray nozzle; and

a fluid supply apparatus, connected to the cleaning/drying spray nozzle to supply the fluid to the cleaning/drying spray nozzle.

11. (original) The system of claim 10, wherein the cleaning solution supply apparatus comprises a temperature adjustment device to control a temperature of the cleaning solution.

12. (original) The system of claim 10, wherein the fluid supply apparatus further comprises a temperature adjustment device to control a temperature of the fluid.

Claims 13-18 (canceled)